

L Number	Hits	Search Text	DB	Time stamp
1	4706	(438/106, 112,124-126,760778,780,781,787).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/17 16:50
2	0	("1 and (epoxy adj4 resin)").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/17 16:51
3	554	((438/106, 112,124-126,760778,780,781,787).CCLS.) and (epoxy adj4 resin)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/17 17:19
4	0	(((438/106, 112,124-126,760778,780,781,787).CCLS.) and (epoxy adj4 resin)) and oxirane	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/17 16:52
5	249	(((438/106, 112,124-126,760778,780,781,787).CCLS.) and (epoxy adj4 resin)) and silicon	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/17 16:52
6	42	(((438/106, 112,124-126,760778,780,781,787).CCLS.) and (epoxy adj4 resin)) and silicon and encapsulate	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/17 17:05
7	4	(((438/106, 112,124-126,760778,780,781,787).CCLS.) and (epoxy adj4 resin)) and silicon and encapsulate and underfill	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/17 17:09
8	2628	(528/10,34,37,40).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/17 17:09
9	117	((528/10,34,37,40).CCLS.) and (epoxy adj4 resin)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/17 17:20
10	0	(((528/10,34,37,40).CCLS.) and (epoxy adj4 resin)) and underfill	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/17 17:20
11	3	(((528/10,34,37,40).CCLS.) and (epoxy adj4 resin)) and (epoxy near silicon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/17 17:21

L Number	Hits	Search Text	DB	Time stamp
1	4145	(257/787,788,789,792,794,795,791).CCLS.	USPAT; US_PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/17 15:46
2	0	("1 and (epoxy adj4 resin)").PN.	USPAT; US_PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/17 15:47
3	934	((257/787,788,789,792,794,795,791).CCLS.) and (epoxy adj4 resin)	USPAT; US_PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/17 15:55
4	331	((257/787,788,789,792,794,795,791).CCLS.) and (epoxy adj4 resin)) and silicon	USPAT; US_PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/17 15:54
5	3	(((257/787,788,789,792,794,795,791).CCLS.) and (epoxy adj4 resin)) and silicon) and oxirane	USPAT; US_PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/17 15:55
6	3	(((257/787,788,789,792,794,795,791).CCLS.) and (epoxy adj4 resin)) and oxirane	USPAT; US_PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/17 15:55

257/787, 788, 789, 792, 794, 795, 791

127, 612

438/106, 112, 124-126/760, 778, 781, 787

528/10, 34, 37, 40, 93, 94, 106, 395

525/109, 523

523/425, 457

06/17/2002

Serial No.: 09/844, 855

FILE 'REGISTRY' ENTERED AT 16:03:49 ON 17 JUN 2002

L1 STRUCTURE UPLOADED
L2 0 S L1 SSS SAM
L3 3 S L1 SSS FULL

FILE 'REGISTRY, MARPAT, MARPATPREV, CAPLUS' ENTERED AT 16:05:01 ON 17 JUN 2002

L4 0 S L1 SSS SAM FILE=REGISTRY
L5 3 S L4 SSS SAM FILE=MARPAT

FILE 'HCAPLUS' ENTERED AT 16:10:21 ON 17 JUN 2002

L6 3 S L3
L7 1 S 3023-55-0/RN
L8 1 S 99791-28-3/RN
L9 1 S 84425-27-4/RN
L10 3 S L7-9

FILE 'REGISTRY' ENTERED AT 16:47:47 ON 17 JUN 2002

L11 1 S 3023-55-0/RN
L12 1 S 99791-28-3/RN
L13 1 S 84425-27-4/RN
L14 3 S L11-13

FILE 'CAOLD' ENTERED AT 16:49:20 ON 17 JUN 2002

L15 1 S L14

FILE 'HCAPLUS' ENTERED AT 16:52:20 ON 17 JUN 2002

=> S L14
L16 3 L14

06/17/2002

Serial No.: 09/844,855

=> D L1
L1 HAS NO ANSWERS
L1 STR

O—Si—O—G2—O—

G1 Ak,H
G2 Cy,Ak

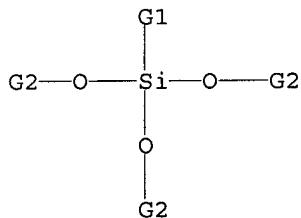
L5 ANSWER 1 OF 3 MARPAT COPYRIGHT 2002 ACS
 AN 136:280893 MARPAT
 TI Storage-stable and antisoiling coating compositions
 IN Matsu Yoichi; Sato, Akira; Tamai, Hitoshi
 PA Kanegafuchi Chemical Industry Co., Ltd., Japan
 SO Jpn. Kokai Tokkyo Koho, 13 pp.
 CODEN: JKXXAF
 DT Patent
 LA Japanese
 FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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PI <u>JP 2002097413</u>	A2	20020402	JP 2000-290560	20000925

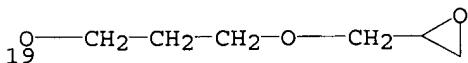
AB Title compns., forming transparent films, comprise 100 parts polymers with a pH of <6, 2-100 parts (R1O)4-aSiR2a (R1, R2 = C1-10 alkyl, aryl, aralkyl; a = 0-1) and/or their partially hydrolyzates, and org. solvents. A compn. comprising Bu acrylate-Me methacrylate-N-methylolacrylamide-3-methacryloxypropyltrimethoxysilane copolymer (as 56% solid soln. with pH 4.6) 100, MS 56S 20, and xylene 10 parts showed good storage stability at 50.degree. for 1 mo. The above compn. was added with more xylene and an org. Sn catalyst, spread on a plate, and aged at 23.degree. and 55% relative humidity for 1 wk to from a film with cloudness 0.1 and low brightness deviation after 3 mo at outdoor.

MSTR 1

What is G2.



G1 = 19



MPL: claim 1

L5 ANSWER 2 OF 3 MARPAT COPYRIGHT 2002 ACS
 AN 120:43914 MARPAT
 TI A film capacitor and method for manufacturing the same
 IN Kamiya, Michiharu; Tachihara, Hisaaki; Otani, Shuji; Yamada, Kenji;
 Kikuchi, Minoru; Iwaoka, Kazuo; Kuwata, Kenji
 PA Matsushita Electric Industrial Co., Ltd., Japan
 SO Eur. Pat. Appl., 29 pp.
 CODEN: EPXXDW
 DT Patent
 LA English
 FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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PI	EP 548996	A2	19930630	EP 1992-122072	19921228
	EP 548996	A3	19940824		
	R: DE, FR, GB				
	JP 05182863	A2	19930723	JP 1991-346017	19911227
	JP 3173087	B2	20010604	JP 1991-346015	19911227
	US 5331504	A	19940719	US 1992-997476	19921228
	CA 2086395	AA	19930628	CA 1992-2086395	19921229
	CA 2086395	C	19971111		

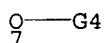
PRAI JP 1991-346015 19911227
 JP 1991-346017 19911227

AB A film capacitor having excellent moisture resistance includes a capacitor element having (a) a multilayer structure made of stacked dielec. films or a wound dielec. film, each dielec. film having a metallic layer formed on its surface, and (b) a pair of outer electrodes elec. connected to the metallic layer, and a coating layer covering the capacitor element. The coating layer is made from at least one polysiloxane, at least one organometallic compd. or a combination of the polysiloxane and the organometallic compd., wherein the organometallic compd. is selected from the group consisting of organoaluminum compds., organosilicon compds., organotin compds. and organotitanium compds. The organometallic compd. has at least one functional group attached to the metallic atom of the organometallic compd., the functional group of which is reactive to inorg. and org. materials and represented by the formula -OR, wherein R is selected from the group consisting of hydrogen, hydrocarbyl, oxygen-contg. hydrocarbyl, nitrogen-contg. hydrocarbyl and oxygen- and nitrogen-contg. hydrocarbyl.

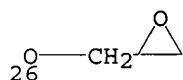
MSTR 1A



G2 = Si
 G3 = OH / 7



G4 = 18



MPL: disclosure

L5 ANSWER 3 OF 3 MARPAT COPYRIGHT 2002 ACS
 AN 115:60906 MARPAT
 TI Printing by forming silicon dioxide film containing organic colorant
 IN Takemura, Kazuo; Ino, Juichi; Kawahara, Hideo; Kitaoka, Masaki
 PA Nippon Sheet Glass Co., Ltd., Japan
 SO Eur. Pat. Appl., 60 pp.

CODEN: EPXXDW

DT Patent

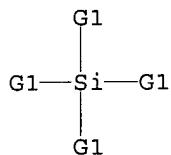
LA English

FAN.CNT 1

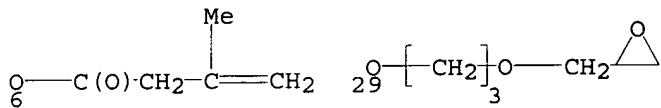
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 391226	A1	19901010	EP 1990-105873	19900328
	EP 391226	B1	19940713		
	R: DE, FR, GB, IT, NL				
JP 03033279	A2	19910213	JP 1989-167366	19890629	

AB Printing of a substrate is achieved by forming thereon a SiO₂ film contg. an org. colorant by contacting the substrate with a processing compn. contg. a silicofluoric acid soln. supersatd. with SiO₂ and forming a SiO₂ film on the substrate, in which an org. colorant is introduced into the SiO₂ film by adding the org. colorant to the processing compn. and a primary film prep'd. from an org. Si compd. having the general formula (R₁)_nSi(R₂)_{4-n} (R₁ = C₁₋₆ hydrocarbyl, vinyl, methacryloxy, epoxy, amino, mercapto, F, or Cl; R₂ = alkoxy, alkoxyalkoxy, or Cl; n = 0-4) is formed on the substrate before the formation of the SiO₂ film.

MSTR 1



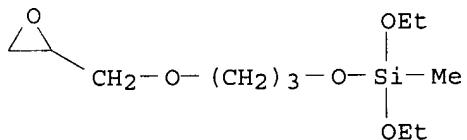
G1 = 6 / 29



MPL: claim 2

L6 ANSWER 1 OF 3 HCAPLUS COPYRIGHT 2002 ACS
AN 1986:34512 HCAPLUS
DN 104:34512
TI Polyester manufacture
IN Mori, Hiroshi; Fujimoto, Masaharu
PA Mitsubishi Rayon Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 3 pp.
CODEN: JKXXAF
DT Patent
LA Japanese

PATENT NO.		KIND	DATE	APPLICATION NO.	DATE
PI	JP 60141719	A2	19850726	JP 1983-248060	19831229
AB	Bis(.beta.-hydroxyethyl) terephthalate or its precondensate is dispersed in a silicone oil by an oligoester-grafted siloxane and heated to give a polyester. Thus, a silicone (prepd. from a cyclosiloxane 50, glycidyl (diethoxymethylsilyl)propyl ether 3, and MeOSiMe3 1 part) 1, PET oligomer 100, and Sb2O3 0.045 part were stirred 30 min at 265.degree., added to 400 parts silicone oil, and stirred 6 h at 265.degree. to give a polyester.				
IT	99791-28-3 RL: USES (Uses) (in grafted siloxane dispersants)				
RN	99791-28-3 HCPLUS				
CN	2,6,8-Trioxa-7-siladecane, 7-ethoxy-7-methyl-1-oxiranyl- (9CI) (CA INDEX NAME)				



L6 ANSWER 2 OF 3 HCAPLUS COPYRIGHT 2002 ACS
AN 1985:221795 HCAPLUS
DN 102:221795
TI Surface treatment of polyurethane resin products
PA Asahi Glass Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 11 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

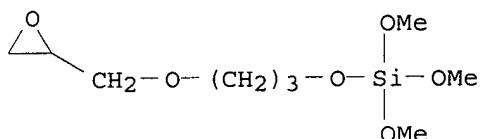
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 60013824	A2	19850124	JP 1983-121525	19830706
	JP 06010227	B4	19940209		
AB	The surface of a polyurethane product can be improved by coating or impregnating with a functional compd. contg. polymerizable unsatn. and .gt;oreq.1 CO ₂ H group and/or moisture-crosslinkable group and irradiating with an energy ray. Thus, a 0.6-mm adipic acid-1,4-butanediol-ethylene glycol-4,4'-methylenebis(cyclohexyl isocyanate) copolymer [39948-98-6] sheet was bonded on one side with a polydimethylsiloxane-coated glass plate and on the other side with a .gamma.-glycidoxypyropyltrimethoxysilane				

[3023-55-0]-coated glass plate, heated at 120.degree. and at 150.degree. and 13 kg/cm² for 30 min, removed from one glass plate, immersed in a soln. of .gamma.-methacryloyloxypropyltrimethoxysilane [2530-85-0] 1432, benzophenone 68, and EtOH 3000 g, and irradiated with UV light of 1000 W to give a laminate with light transmittance 90% (JIS R 3212).

IT 3023-55-0

RL: USES (Uses)
(coatings, for glass-polyurethane laminates)

RN 3023-55-0 HCPLUS

CN Silicic acid (H₄SiO₄), trimethyl 3-(oxiranylmethoxy)propyl ester (9CI)
(CA INDEX NAME)

L6 ANSWER 3 OF 3 HCPLUS COPYRIGHT 2002 ACS

AN 1983:55769 HCPLUS

DN 98:55769

TI Moisture-curable siloxane sealants

PA Toshiba Silicone Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 8 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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PI JP 57141447 A2 19820901 JP 1981-26891 19810227

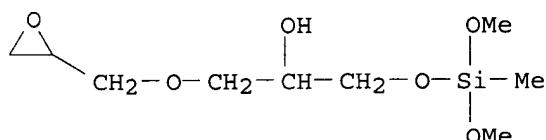
AB Moisture-curable sealants contain hydroxy-terminated siloxanes 100, silanes having oxiranylalkoxy groups 1-25, and catalysts 0.01-10 parts. Thus, a hydroxy-terminated siloxane (viscosity 20,000 cSt at 25.degree.) 90, colloidal silica 10, bis(glycidyloxy)methylmethoxysilane [58213-71-1] 4.2, methyltris(glycidyloxy)silane [58213-70-0] 1.8, tris(3-trimethoxysilylpropyl) isocyanurate 0.2, and Bu₂Sn dilaurate [77-58-7] 0.5 part were mixed in a dry atm., and formed into a 2-mm sheet. The sheet was dried to the touch after 10 min in the air, and after 72 h of curing in the air it had tensile strength 16 kg/cm², hardness 25, elongation 480%, and good adhesion to glass and steel (100% cohesive failure).

IT 84425-27-4

RL: MOA (Modifier or additive use); USES (Uses)
(crosslinking agents, for moisture-curable siloxane sealants)

RN 84425-27-4 HCPLUS

CN 2,4,8-Trioxa-3-silaninan-6-ol, 3-methoxy-3-methyl-9-oxiranyl- (9CI) (CA INDEX NAME)



06/17/2002

Serial No.: 09/844,855

